

IN THE SPECIFICATION:

The specification as amended below with replacement paragraphs shows added text with underlining and deleted text with ~~striketrough~~.

Please REPLACE paragraph [0007] on page 2 with the following amended paragraph:

[0007] Such a photolithographic method can be used before an organic film is formed, but causes a problem when it is used after an organic film is formed. Because the organic film is very sensitive to water, it must be thoroughly isolated from water both while being fabricated and after the fabrication. Consequently, a photolithographic method including an exposure to water during ~~peeling-off~~ peeling-off and etching of a resist is not suitable for patterning the organic film and the second electrode layer.